

AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A method for fabricating a reflective plate used in a liquid crystal display comprising:

depositing a first organic insulating layer on a substrate;

forming a first peak and depression layer in a plurality of first peak patterns having a predetermined distance from the first organic insulating layer by using a first mask;

depositing a second organic insulating layer on the first peak and depression layer the substrate including the first peak patterns;

forming a second peak and depression layer in a plurality of second peak patterns between the first peak patterns from the second organic insulating layer by using a second mask;
and

forming a reflective electrode on the first and second peak patterns ~~the first and second peak and depression layers;~~

~~wherein the first and second peak and depression layers each overlap a predetermined area and have different heights~~ the second peak patterns have a different height from the first peak patterns, and overlap only a portion of the adjacent first peak pattern.

2. (Currently Amended) The method according to claim 1, wherein the first and second peak patterns ~~the first and second peak and depression layers~~ are softened by a curing bake process to form a plurality of peak patterns.

3. (Currently Amended) The method according to claim 1, wherein each of the first peak patterns ~~the first peak and depression layer~~ comprises a plurality of first peaks and each of the second peak pattern ~~the second peak and depression layer~~ comprises a plurality of second peaks, wherein a highest point of each of the first peaks is located at different locations from a highest point of each of the second peaks.

4. (Currently Amended) The method according to claim 1, wherein each of the first peak patterns ~~the first peak and depression layer~~ comprises a plurality of first peaks and each of the second peak pattern ~~the second peak and depression layer~~ comprises a plurality of second

peaks, wherein a center of each of the first peaks is located at different locations from a center of each of the second peaks.

5. (Currently Amended) The method according to claim 1, wherein the first and second organic insulating layers are photosensitive resin.

6. (Original) The method according to claim 1, wherein the first mask comprises a light transmission portion and a light reflecting portion.

7. (Original) The method according to claim 1, wherein the second mask comprises a light transmission portion and a light reflecting portion.

8. (Original) The method according to claim 1, wherein the first mask is one of a transflective mask and a diffraction mask.

9. (Original) The method according to claim 1, wherein the second mask is one of a transflective mask and a diffraction mask

10. (Currently Amended) The method according to claim 1, wherein the first and second peak patterns ~~the first and second peak and depression layers~~ have a plurality of peaks that are randomly arranged.

11. (Currently Amended) The method according to claim 1, wherein each of the first peak patterns ~~the first peak and depression layer~~ comprises a plurality of first peaks and each of the second peak pattern ~~the second peak and depression layer~~ comprises a plurality of second peak overlapped with the first peaks.

12. (Currently Amended) The method according to claim 1, wherein each of the first peak patterns ~~the first peak and depression layer~~ comprises a plurality of first peaks and each of the second peak pattern ~~the second peak and depression layer~~ comprises a plurality of second peaks overlapped with portions of the first peaks with a height less than one half height of the first peaks.

13. (Currently Amended) The method according to claim 1, wherein a reflecting surface formed by the first and second peak patterns ~~the first and second peak and depression layers~~ has final peak shapes in which a ratio of a height to a radius of the peak is 1:10.

14. (Withdrawn) A reflective plate used in a liquid crystal display comprising:
a substrate;
a first peak and depression layer of organic insulator on the substrate;
a second peak and depression layer of organic insulator overlapping with the first peak and depression layer; and
a reflective layer on the first and second peak and depression layers.

15. (Withdrawn) The reflective plate according to claim 14, wherein the organic insulator is a photosensitive resin film.

16. (Withdrawn) The reflective plate according to claim 14, wherein the first peak and depression layer has a plurality of first peaks and the second peak and depression layer has a plurality of second peaks, wherein a highest point of each of the first peaks is located at different locations from a highest point of each of the second peaks.

17. (Withdrawn) The reflective plate according to claim 14, wherein the first peak and depression layer comprises a plurality of first peaks and the second peak and depression layer comprises a plurality of second peaks, wherein a center of each of the first peaks is located at different location from a center of each of the second peaks.

18. (Withdrawn) The reflective plate according to claim 14, wherein the first peak and depression layer comprises a plurality of first peaks and the second peak and depression layer comprises a plurality of second peaks overlapped with the second peaks.

19. (Withdrawn) The reflective plate according to claim 14, wherein the first and second peak and depression layers have a plurality of peaks that are randomly arranged.

20. (Withdrawn) The reflective plate according to claim 14, wherein the first peak and depression layer comprises a plurality of first peaks and the second peak and depression layer comprises a plurality of second peaks overlapped with portions of the first peaks with a height less than one half height of the first peaks.

21. (Withdrawn) The reflective plate according to claim 14, wherein a reflecting surface formed by the first and second peak and depression layers has final peak shapes in which a ratio of a height to a radius of the peak is 1:10.

22. (New) The method according to claim 1, wherein the second peak patterns between the first peak patterns directly contacts the substrate.